# Non-Volatile Reconfigurable Transmissive Notch Filter Using Wide Bandgap Phase Change Material Antimony Sulfide

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Abstract-Reconfigurable free-space metasurfaces with subwavelength-scale tunable nano-scatterers can manipulate light for many applications ranging from bio-medical imaging, light detection and ranging to optical computing. Several endeavors have been made to achieve tunable metasurfaces using thermo-optic, electro-optic effects, liquid crystals, and phase change materials (PCMs). PCMs stand out, particularly for low-tuning frequency and low-power consumption applications, thanks to their nonvolatile nature and drastic index modulation, leading to zero-static power and a small footprint. Antimony sulfide (Sb<sub>2</sub>S<sub>3</sub>) is an emerging low-loss PCM with the widest bandgap reported so far, enabling operation at low wavelengths down to  $\sim$ 600 nm in the visible spectrum. In addition, Sb<sub>2</sub>S<sub>3</sub> has slow crystallization speed, which enables amorphization of large-volume Sb<sub>2</sub>S<sub>3</sub> without unintentional recrystallization. This makes Sb<sub>2</sub>S<sub>3</sub> suitable for application in reconfigurable metasurfaces, where the switching area (usually > hundreds of  $\mu$ m<sup>2</sup>) is significantly larger than photonic integrated circuits (tens of  $\mu m^2$ ). Herein, we experimentally demonstrate an electrically tunable notch filter at a wavelength of  ${\sim}1150$  nm on a Sb<sub>2</sub>S<sub>3</sub>-cladded silicon-on-sapphire platform. The notch filter is enabled by a 2-dimensional symmetry-protected quasi-boundstate-in-the-continuum (quasi-BIC) metasurface. We experimentally observed a quality factor of up to  $\sim 200$  and demonstrated reversible tuning of a record large volume (4.5  $\mu$ m<sup>3</sup>) of Sb<sub>2</sub>S<sub>3</sub>. Thanks to the large modulation provided by Sb<sub>2</sub>S<sub>3</sub>, we observed a resonance shift as high as  $\sim$ 4 nm in situ using a doped silicon microheater. Our work paves the way for compact and low-power nonvolatile notch filters. Moreover, due to the low loss of Sb<sub>2</sub>S<sub>3</sub>

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in the visible, this work also lays the foundation for phase-only modulation in the visible using PCMs.

*Index Terms*—Antimony sulfide, bound states in the continuum, metasurface, notch filter, phase change material.

## I. INTRODUCTION

ETASURFACES consisting of subwavelength scale nano-scatterer arrays can precisely manipulate light, finding numerous applications in bio-medical sensing [1], endoscopy [2], wireless communication [3], spectroscopy [4], light detection and ranging [5], and recently even optical computation and artificial intelligence [6], [7]. Post-fabrication reconfigurability [8] of such metasurfaces is generally desired and has been carried out using the thermo-optic effect [9], the electro-optic effect [10], liquid crystals (LCs) [11] or phase change materials (PCMs) [12], [13], [14], [15], [16], [17], [18], [19]. PCMs have numerous benefits over other approaches, primarily in that they provide nonvolatile and sizeable refractive index modulation upon transition between their amorphous(a)- and crystalline(c)phases ( $\Delta n \sim O(1)$  [13]). This leads to a "set-and-forget" operation with a compact device footprint critical for large-scale optical systems. Traditionally, PCMs such as Ge<sub>2</sub>Sb<sub>2</sub>Te<sub>5</sub> (GST) were mainly used in electronic memory applications and are sub-optimal for optical usage primarily because of their high absorptive losses in both a-, c- states in the visible or nearinfrared (NIR) range. This precludes their usage for phase-only modulation in the NIR range and poses even more challenges to exploit them in the visible.

On the other hand, emerging wide bandgap PCM antimony sulfide (Sb<sub>2</sub>S<sub>3</sub>) [20] exhibits negligible optical loss both in its a- and c- states in the NIR spectrum. This emerging material provides an excellent solution to tuning any resonant structure without breaking desired resonant behavior, beyond the capability of GST. Furthermore, Sb<sub>2</sub>S<sub>3</sub> is the only reversibly switchable PCM with low loss down to the visible spectrum (~600 nm) reported so far, making it attractive for visible frequency metasurfaces. Besides all these advantages, the slow crystallization process of Sb<sub>2</sub>S<sub>3</sub>, as observed in this work and demonstrated previously in photonic integrated circuits [21], enables large area switching thanks to no unintentional recrystallization during the

1077-260X © 2024 IEEE. Personal use is permitted, but republication/redistribution requires IEEE permission. See https://www.ieee.org/publications/rights/index.html for more information. amorphization process. This is critical for free-space reconfigurable metasurfaces where the switching area (> thousands of  $\mu$ m<sup>2</sup>) is generally much larger than integrated photonic circuits (tens of  $\mu$ m<sup>2</sup>). Previous works on Sb<sub>2</sub>S<sub>3</sub> have mainly relied on laser pulses to switch Sb<sub>2</sub>S<sub>3</sub> [22], [23], [24], which is ex-situ and requires a well-aligned, bulky, and sophisticated pulsed laser setup, significantly limiting its usage. Although previous works demonstrated using ITO heaters [25] or doped silicon *p-i-n* heaters [21] to reversibly switch Sb<sub>2</sub>S<sub>3</sub> in PICs, the challenge remains to switch a large volume of Sb<sub>2</sub>S<sub>3</sub> for electrically reconfigurable metasurfaces.

Here, we experimentally demonstrate an electrically tunable notch filter based on a symmetry-protected quasi-BIC metasurface. The notch filter operates at a wavelength of  $\sim 1150$  nm on a Sb<sub>2</sub>S<sub>3</sub>-cladded silicon-on-sapphire platform via doped silicon microheaters. We experimentally observe a quality factor up to  $\sim 200$  and demonstrate reversible tuning of a large volume  $(\sim 4.5 \ \mu m^3)$  of Sb<sub>2</sub>S<sub>3</sub>. The device produced a resonance shift of up to  $\sim$ 4 nm, amplitude attenuation of  $\sim$ 40%, and an amplitude modulation of  $\sim$ 30%. Non-volatile tunable notch filters are promising solutions to reconfigurable optical spectral filters with zero static power consumption. Moreover, they have strong potential for low-power displays [22], phase-only transmissive spatial light modulators [18], [26] and augmented reality displays which require localized dimming of selected pixels [12]. Our work paves the way for compact, low-power non-volatile notch filters.

# II. DESIGN OF RECONFIGURABLE SYMMETRY-PROTECTED QUASI-BIC METASURFACES

Fig. 1 shows our design of the 2-dimensional periodic metasurface, which supports a symmetry-protected BIC mode [27], [28], [29], [30]. Each unit cell contains two partially etched Si nano-bars, and the geometry and material layers are shown in Fig. 1(a)–(d). The periods along x- and y-directions  $(P_x \text{ and } P_y)$ are 710 and 536 nm, respectively and the distance between the nano-bars was kept constant as 177.5 nm. The length, width  $(N_y \text{ and } N_x)$  and height (H) of the nano-bars are 340, 110 and 240 nm, respectively. A doped silicon microheater is formed by keeping 100 nm(h) of Si un-etched underneath the metasurface. We optimize the microheater by adding a curvature on the edge to uniformly heat the metasurface and to switch a larger area of the PCM [31]. In contrast, a rectangular heater has much larger temperature gradients (Fig. 6) across the heating area, incurring a much higher temperature at the metasurface center and hence material ablation. This was also confirmed in the experiment (Fig. 7).

For normal incidence our device supports a BIC mode at a free-space wavelength of  $\lambda \sim 1093$  nm in case of the silicon only metasurface. For a rotation angle of 0° between the nanobars, the structure possesses a mirror symmetry along the x axis. The electric field profile ( $E_x$ ) of the BIC mode is odd with respect to the mirror transformation (y)  $\rightarrow$  (-y), while the incident illumination (x polarized) is even [32]. This mismatch prevents the mode from coupling to the incident radiation, causing it to



Fig. 1. Design of a symmetry-protected quasi-BIC meta surface. (a) Schematic of the device. (b) Zoomed-in schematic of the metasurface. (c) Zoomed-in schematic of a single unit cell.  $P_x$  and  $P_y$  denote the period of the metasurface in the x and y directions (710 nm and 536 nm, respectively).  $N_x$  and  $N_y$  denote the width and length of the nano-bars (340 nm and 110 nm), respectively. *H* is the height of the nano-bars, which was kept at 240 nm. *h* is the thickness of the partially etched silicon layer, kept at 100 nm. (d) Cross-section of a single unit cell showing different material layers. (e) Simulated transmission plot of silicon-only metasurface with respect to different wavelengths and rotation angles for x polarized incident illumination. The BIC mode is dark for an asymmetry factor of 0. The color bar represents the transmission value. (f) Simulated spectrum for both a- and c-Sb<sub>2</sub>S<sub>3</sub>. A resonance shift of ~5 nm is observed for a quasi-BIC mode with an asymmetry parameter of 13°.



Fig. 2. Fabricated quasi-BIC metasurface (a) optical micrograph of the fabricated device. (Scale bar: 15  $\mu$ m) (b) Zoomed-in image of the metasurface. (Scale bar: 110 nm) (b) scanning electron microscope (SEM) image of the silicon nano-bars. (Scale bar: 1.5  $\mu$ m) (d) zoomed-in SEM image for a single unit cell after Sb<sub>2</sub>S<sub>3</sub> and alumina deposition. (Scale bar: 40 nm).



Fig. 3. Schematic of the setup used to characterize the fabricated sample.

have an infinite Q factor. This manifests itself in the absence of any resonance features in the transmission spectrum of the structure for a rotation angle of  $0^{\circ}$  (Fig. 1(e)). Breaking the in-plane mirror symmetry about the x axis by having a non-zero rotation angle instead of changing the incident angle [29] leads the field profile not being perfectly odd (see Figs. 8, 9 and 10) with respect to the same mirror symmetry leading to the coupling of the BIC mode to free-space radiation. This transforms the mode into a quasi-BIC mode with a finite resonance linewidth. The rotation angle governs the coupling rate of the mode to the radiative continuum spectrum, and therefore is an effective knob to tune the resonance linewidth of the notch-filter.

Reconfigurability is achieved by cladding the metasurface with 20 nm of  $Sb_2S_3$  encapsulated by 40 nm of alumina. The encapsulation is crucial to protect the  $Sb_2S_3$  from sulfur loss, oxidation and thermal reflowing during the high temperature phase transition process, hence reversible phase transitions [33]. Fig. 1(f) shows the simulated transmission spectrum for both aand c-Sb\_2S\_3 and a large resonance shift of ~5 nm is achieved with only 20 nm of  $Sb_2S_3$ . We picked this operation wavelength (~1150 nm) to demonstrate the transparency of  $Sb_2S_3$  at a relatively short wavelength, which is already beyond the capability of most of the prominent PCMs like GST and  $Ge_2Sb_2Se_4Te_1$ (GSST) [12]. Moreover, the operating wavelength can be finetuned by scaling the unit cells uniformly (Fig. 11), providing a convenient way to design for different operation wavelengths.

#### **III. MATERIALS AND FABRICATION**

### A. Device Fabrication and Characterization Setups

The sample was fabricated from a 500-nm-silicon on sapphire (SOS) chip. The wafer was implanted by phosphorous ions with a dosage of  $2 \times 10^{15}$  ions per cm<sup>2</sup>, ion energy of 40 keV and a tilt angle of 7°. It was then annealed at 950 °C (Expertech CTR200 Anneal Furnace) for 30 minutes to activate the dopants and to get a uniform dopant concentration of  $\sim 10^{18}$  cm<sup>-3</sup>. Then the silicon was thinned down to 340 nm using an inductively coupled plasma reactive ion etching etcher (ICP-RIE, Oxford Instruments PlasmaLab 100) with Fluorine gas chemistry. 300-nm-thick positive-tone E-beam resist (ZEP-520A) was then spin coated followed by a discharge layer (DisCharge  $H_2O$ ). The resist was then patterned using E-beam lithography (JEOL JBX6300FS) and the pattern transferred onto the silicon layer using Fluorine-based ICP-RIE. After stripping the resist, Sb<sub>2</sub>S<sub>3</sub> was deposited using DC sputtering (Lesker Sputter Lab 18) and immediately encapsulated with 40-nm Al<sub>2</sub>O<sub>3</sub> using atomic layer deposition (Oxford Instruments PlasmaLab 80plus OpAl ALD). The sample was then annealed (Allin21 Corp Rapid Thermal Annealer - RTA) at 325 °C in Nitrogen environment for 10 minutes to crystallize the Sb<sub>2</sub>S<sub>3</sub>. Following this, negative photoresist (NR9G-3000PY) was spin coated onto the sample and patterned using direct laser writing lithography (Heidelberg DWL66+) to define the metal contacts. Before the metallization, Al<sub>2</sub>O<sub>3</sub> and Sb<sub>2</sub>S<sub>3</sub> were etched using a chlorine-based ICP-RIE etcher (Oxford Instruments PlasmaLab 100) to ensure an ohmic contact. Then, a room temperature DC sputterer (Evatec LLS EVO) was used to deposit Titanium/ Platinum (10/180 nm) followed by photoresist lift-off in acetone accompanied with



Fig. 4. Experimentally measured transmission spectrum of  $Sb_2S_3$  cladded metasurface for rotation angle of (a) 0°, (b) 13°, (c) 15°, (d) 17° with  $Sb_2S_3$  in the crystalline state. A direct dependence of the full-width-half-maximum (FWHM) on the rotation angle is observed, matching well with the simulation.



Fig. 5. Characterization results of the electrically reconfigurable metasurface. (a) A 15 × 15  $\mu m^2$  device on a curved doped silicon heater. (Scale bar: 2  $\mu$ m) (b) Crystallized Sb<sub>2</sub>S<sub>3</sub> after RTA at 325 °C. (Scale bar: 3  $\mu$ m). (c) Amorphous Sb<sub>2</sub>S<sub>3</sub> after a 20-V, 4- $\mu$ s pulse, a visible change in color was seen between a- and c-Sb<sub>2</sub>S<sub>3</sub>. Also, a-Sb<sub>2</sub>S<sub>3</sub> shows a more uniform color, in absence of white dot-like crystallites. (Scale bar: 3  $\mu$ m). (d) c-Sb<sub>2</sub>S<sub>3</sub> after 9-V DC voltage. (Scale bar: 3  $\mu$ m). (e) Material ablated due to a 20-V, 15- $\mu$ s pulse. (f) Transmission spectrum of the metasurface for a- and c-Sb<sub>2</sub>S<sub>3</sub> at the 8<sup>th</sup> cycle. The FWHM of the metasurface for a(c)-Sb<sub>2</sub>S<sub>3</sub> is 8.7 (10.5) nm. (g) Extracted resonant wavelength for a- and c-Sb<sub>2</sub>S<sub>3</sub> along 9 switching cycles, showing little performance degradation.

gentle sonication. In this case, sputtering was preferred over E-beam evaporation to avoid exposing the  $Sb_2S_3$  to high temperatures, specifically temperatures above its ablation point. Finally, another step of direct laser writing lithography was performed to isolate the devices electrically with a positive-tone photoresist (AZ-1512). The silicon was then fully etched from the exposed areas using the Fluorine-based ICP-RIE etcher. Fig. 2 shows the micrographs and scanning electron microscope images of the fabricated device. Fig. 12 shows the diagram of various fabrication steps.

# IV. CHARACTERIZATION OF THE ELECTRICALLY RECONFIGURABLE METASURFACE

## A. Setup

Fig. 3 shows the schematic of our measurement setup. The sample was illuminated using a broadband laser (WhiteLase

Micro). The laser light was first collimated using Lens 1, after which it was focused onto the sample using a  $10 \times$  objective (Objective 1) of 0.26 numerical aperture (NA). The Dichroic Mirror 1 is used to deflect the reflected light from the metasurface to a camera (Camera 1 – Thorlabs CS165MU) along with an imaging lens (Lens 2). The transmitted light from the sample is collected using a  $50 \times$  objective (Objective 2) with NA 0.65 and again split into an infrared camera (Camera 2 - Pembroke SenS SWIR) with imaging lens (Lens 3). Finally, the laser light is fiber coupled using Lens 4 and fed to the infrared sensor (Teledyne Pylon IR) and the spectrometer (Princeton Instruments Acton SpectraPro SP-2750). The electrical measurements were carried out using a pair of electrical probes on two probe positioners (Cascade Microtech DPP105-M-AI-S). The electrical pulses were generated from a arbitrary function generator (Keysight 81160 A).

# B. Results

We first measure the spectrum of the devices to find the quasi-BIC mode. We observed the designed mode at ~1150 nm. No measurable resonance was observed as shown in Fig. 4(a) for the device with rotation angle 0, indicating a dark BIC state. Whereas the asymmetrical devices in Fig. 4(b)–(d) produced a direct dependence of the FWHM with the rotation angle of the nano-bars, indicating a quasi-BIC state in excellent agreement with the simulation. We note that the quality factor is limited by fabrication imperfections and the high doping concentration of silicon (~10<sup>18</sup> cm<sup>-3</sup>) which adds extra absorption loss due to free-carrier dispersion effect (Fig. 13).

The amorphization process requires melting and quenching the Sb<sub>2</sub>S<sub>3</sub> rapidly below its glass transition temperature, and the required cooling rate (>1 K  $\cdot$  ns<sup>-1</sup>) determines the area of Sb<sub>2</sub>S<sub>3</sub> that can be switched reversibly. Here, we use a design of experiment approach to optimize the size of the meta surface - multiple devices of varying areas were fabricated on the same chip. Fig. 5(a) and (b) shows the microscope image of an as-fabricated c-Sb<sub>2</sub>S<sub>3</sub> device of an area  $15 \times 15 \ \mu m^2$  with the curved heater design. To change the Sb<sub>2</sub>S<sub>3</sub> from c- to a-phase (amorphization), high-amplitude (20 V), relatively short duration (4  $\mu$ s) electrical pulses were applied to produce a visual color change under the microscope in Fig. 5(c). After that, the sample was annealed under 325 °C for 10 mins to recrystallize Sb<sub>2</sub>S<sub>3</sub>, a similar microscope image as in Fig. 5(b) was observed, indicating that the  $Sb_2S_3$  was switched reversibly. Later, crystallization was also induced electrically by applying a low amplitude (9 V), DC voltage. The micrograph after the applied crystallization voltage is shown in Fig. 5(d). The switching condition was then again verified by measuring the transmission spectrum of the metasurface. Ablated devices such as in Fig. 5(e) did not switch back due to the permanent material damage, hence no color change. We note that the high voltage requirement can be mainly attributed to the high resistance of our devices ( $\sim$ 200 ohms). This can be improved by further optimizing the doping profile and increasing the doped silicon microheater thickness. Additionally, the thermal performance can also be improved by changing the substrate material. Since sapphire has

a much higher thermal conductivity ( $\sim$ 30 W/m · K) than SiO<sub>2</sub> ( $\sim$ 1 W/m · K) at room temperature, a higher heat dissipation in Al<sub>2</sub>O<sub>3</sub> leads to inefficient heating. Therefore, replacing the substrate to SiO<sub>2</sub> or even suspending the metasurface membrane in air could significantly improve power efficiency.

Thanks to the uniform heating, 9 cycles of reversible switching were achieved with little performance degradation. Fig. 5(f) shows the measured transmission spectrum after 8 cycles. As expected, we observe a red-shift and Q-factor reduction after crystallization since c-Sb<sub>2</sub>S<sub>3</sub> has a larger refractive index and absorptive loss (see Fig. 14). The losses of  $c-Sb_2S_3$  can be mainly attributed to scattering of light due to the crystal grain boundaries, which can be minimized by reducing the grains size [34]. Furthermore, as c- to a- switching requires melting and rapid quenching of the material, quenching should be fast enough to avoid the onset of the crystallization process. Therefore, amorphization pulses in electro-thermal heaters are generally in the scale of hundreds of nanoseconds [35], [36]. However as observed in this work and previously reported [21], Sb<sub>2</sub>S<sub>3</sub> can be switched from c- to a- state using  $>1 \mu$ s pulses. This indicates that the crystallization process in Sb<sub>2</sub>S<sub>3</sub> is slower compared to PCMs such as GST [21], [35], leading to a much-relaxed critical cooling rate requirement and thus ability to switch large volume. The theoretical and practical upper limit of such a volume remains to be determined. We also show thermo-optic tuning of the resonance in Fig. 15. The thermal simulation results of a 20V  $4 \,\mu s$  pulse are shown in Fig. 16. The tunable notch filter produced a resonance shift of up to  $\sim 4$  nm, amplitude attenuation of 2.5 dB at the resonance wavelength in amorphous state and an amplitude modulation of  $\sim$  30% due to PCM switching from a- to c- Sb<sub>2</sub>S<sub>3</sub>. The resonance wavelengths across 9 cycles are plotted in Fig. 5(g), showing little device degradation. A slight increase in the contrast can be attributed to a "conditioning" process for initial crystallite formation. We also characterized a larger device with an area of  $20 \times 16 \,\mu\text{m}^2$  on a rectangular heater (Fig. 17). We were able to switch the device for 2 cycles. This demonstrates the difficulty of switching large volume Sb<sub>2</sub>S<sub>3</sub> and we emphasize that this work showcases the largest Sb<sub>2</sub>S<sub>3</sub> area ( $15 \times 15 \ \mu m^2$ ) that has been electrically and reversibly switched so far.

## V. CONCLUSION

In summary, we have designed, fabricated, and experimentally demonstrated a reconfigurable non-volatile notch-filter based on a symmetry-protected quasi-BIC metasurface with high Q-factor of  $\sim$ 200. The active modulation was provided by a 20-nm-thick layer of PCM Sb<sub>2</sub>S<sub>3</sub>, which was electrically controlled in situ by doped silicon microheaters. An amplitude attenuation of 2.5 dB and modulation of  $\sim$ 30% was achieved at  $\sim$ 1150 nm. We further showed reversible switching of large area of  $Sb_2S_3$  (15 × 15  $\mu$ m<sup>2</sup>) up to 9 cycles with little performance degradation. In the future, we need to achieve lower voltage operation, higher extinction ratio, and larger number of switching cycles. Our work shows that wide-band gap PCMs are promising for phase-only modulations. Besides, due to low loss of Sb<sub>2</sub>S<sub>3</sub> in the visible, this work also lays the foundation for applications of PCMs for phase-only modulation in visible-wavelength metasurfaces.



Fig. 6. 3D Thermal simulations for two different types of heater geometry. Compared to the rectangular geometry, the curved heater design can reduce the temperature variation from the edge to the center significantly, from 140 K to 80 K. The Silicon under the metal pads is 340 nm thick and under the metasurface the thickness if 100 nm.



Fig. 7. Switching of  $15x11 \ \mu m^2$  device on a rectangular heater. (a) A 15  $\times 11 \ \mu m^2$  device on a rectangular doped silicon heater. (Scale bar: 4  $\mu m$ ). (b) c-Sb<sub>2</sub>S<sub>3</sub> after RTA at 325 °C. (Scale bar: 4  $\mu m$ ). (c) Visible material ablation after application of a 20V 4- $\mu$ s electrical pulse. We attribute this to the concentration of very high temperature at the center of the device. (a) Micrograph of a 15  $\times$  11  $\mu$ m<sup>2</sup> device. (Scale bar: 4  $\mu$ m).



Fig. 8.  $E_x$  field profiles inside the unit cell at  $\lambda_0 \sim 1093$  nm for asymmetry angle 13° in the case of silicon only metasurface. The simulation was performed using the Lumerical FDTD solver.



Fig. 9. Ex field profile inside the unit cell for asymmetry angle  $13^\circ$  and c-Sb\_2S\_3 at  $\lambda_0 \sim\!\! 1146$  nm.



Fig. 10. Ex field profile inside the unit cell for asymmetry angle 0° and c-Sb<sub>2</sub>S<sub>3</sub> at  $\lambda_0 \sim 1146$  nm. The simulation was performed using a dipole cloud as the illumination source.



Fig. 11. Resonance wavelength for 3 different scaling factors in the case of the silicon only metasurface. A red(blue) shift occurs when increasing (decreasing) the size of the unit cell. A scaling factor of 0.99 means that all the dimensions of the unit cell in the *x*- and *y*- directions were multiplied by 0.99.



Fig. 12. The fabrication process flow Various steps followed to fabricate the reconfigurable metasurface.



Fig. 13. Refractive index data of 230 nm doped Silicon on Sapphire measured using variable angle ellipsometry (woollam RC2).



Fig. 14. Refractive index and extinction ratio values of 20 nm thick  $Sb_2S_3$  used for simulations. The optical constants were measured using variable angle ellipsometer woollam RC2.



Fig. 15. Tuning via thermo-optic effect Change in the resonant wavelength of the Quasi-BIC mode after application of 6V DC due to thermo-optic effect.



Fig. 16. 2D heat transfer simulation Plot and thermal distribution of a 20 V  $4 \ \mu s$  pulse.



Fig. 17. Reversible tuning of a  $20 \times 16 \ \mu\text{m}^2$  device for up to 2 cycles. Plot shows the 2nd cycle which had a resonance shift of  $\sim 2 \text{ nm}$ . A high voltage (20 V), 10  $\mu$ s pulse was applied to switch the device. A relatively low-voltage (13 V) DC voltage was subsequently applied to re-crystallize Sb<sub>2</sub>S<sub>3</sub>.

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